

Micropatterning Japan TC Meeting Summary and Minutes

SEMI Japan Standards Fall 2014 Meetings
Wednesday, October 8, 2014, 15:30-17:00
SEMI Japan, Tokyo, Japan

Next Committee Meeting

SEMI Japan Standards Winter 2015 Meetings
Thursday, January 29, 2015, 15:30-17:00
SEMI Japan, Tokyo, Japan

Table 1 Meeting Attendees

Co-Chairs: Morihisa Hoga (Dai Nippon Printing)

SEMI Staff: Naoko Tejima (SEMI Japan)

<i>Company</i>	<i>Last</i>	<i>First</i>	<i>Company</i>	<i>Last</i>	<i>First</i>
Yotta Data Sciences (teleconference)	Grebinski	Thomas	Dai Nippon Printing	Suzuki	Toshio
Dai Nippon Printing	Hoga	Morihisa	SEMI Japan	Tejima	Naoko
-	Otaki	Masao			

** alphabetical order by last name*

Table 2 Leadership Changes

None

Table 3 Ballot Results

Passed ballots and line items will be forwarded to the ISC Audit & Review Subcommittee for procedural review.

Failed ballots and line items were returned to the originating task forces for re-work and re-balloting.

<i>Document #</i>	<i>Document Title</i>	<i>Committee Action</i>
5229	Revision to SEMI P44-0211, Specification for Open Artwork System interchange Standard (OASIS [®]) Specific to Mask Tools	Passed with editorial changes

Table 4 Authorized Activities

None

Table 5 New Action Items

<i>Item #</i>	<i>Assigned to</i>	<i>Details</i>
MP120828-2	5 Year Review Task Force	To draft the document of Doc. 5484, Revision to SEMI P22-0307 to submit it for the earliest possible cycle.
MP121211-1	5 Year Review Task Force	To draft the document of Doc. 5537, Line Item Revision to SEMI P23-0200 to submit it for the earliest possible cycle.
MP130828-1	5 Year Review Task Force	To draft the background statements for the Document #5484 and #5537
MP141008-1	SEMI Staff	To forward adjudication result of Doc.#5229 to the ISC A&R Subcommittee for procedural review.

1 Welcome, Reminders and Introductions

Morihsa Hoga, committee co-chair, called the meeting to order at 15:30. Self-introductions were made followed by the agenda review.

2 Required Meeting Elements

The meeting reminders on program membership requirement, antitrust issues, intellectual property issues and international effective meeting guidelines, were reviewed by SEMI staff, Naoko Tejima.

3 Review of Previous Meeting Minutes

The committee reviewed the minutes of the previous meeting held on April 23, 2014.

Motion: To approve the minutes of the previous meeting as submitted.

By / 2nd: Toshio Suzuki (Dainippon Printing) / Masako Otaki (-)

Discussion: None

Vote: 2 in favor and 0 opposed. **Motion passed.**

Attachment: 01_JA_Micropatterning_Previous_Mtg_Minutes_141008

4 SEMI Staff Report

Naoko Tejima gave the SEMI staff report. This report included PV Automation TC Transformation to Automation Technology TC, New Task Force Operation Guideline, SEMI Global 2014 & 2015 Calendar of Events, Global Standards Meeting Schedule, SEMICON Europa 2014 Meetings, NA Fall Standards Meetings, SEMICON Japan 2014 Information, 2014 Critical Dates for SEMI Standards Ballots, SEMI Standards Publication, A&R Ballot Review and Contact Information.

Attachment: 02_SEMI_Staff_Report_141008

Attachment: 03_Task_Force_Operation_Guideline_141008

5 Liaison Reports

5.1 Microlithography North America TC Report

Naoko Tejima briefly reported for the Microlithography North America TC. This report included Task Force and Leadership Changes, Leadership, Microlithography TC Chapter Structure, Meeting Information, Document Review Summary, New Activities, Task Force Updates, Five-year Review Status and Contact Information.

Attachment: 04_Microlithography_NA_TC_Report_Oct2014_141008

6 Ballot Review

6.1 *Doc.#5229, Revision to SEMI P44-0211, Specification for Open Artwork System interchange Standard (OASIS[®]) Specific to Mask Tools.*

This document passed committee review with editorial changes and will be forwarded to the ISC A&R SC for procedural review.

Action Item: SEMI staff to forward adjudication result of Doc.#5229 to the ISC A&R Subcommittee for procedural review.

Attachment: 05_Ballot_Report_for_5229_141008

7 Task Force Reports

7.1 Mask Data Format for Mask Tools Task Force

Toshio Suzuki reported for the Mask data Format for Mask Tools Task Force. Of note:

- *Doc.#5229, Revision to SEMI P44-0211, Specification for Open Artwork System interchange Standard (OASIS®) Specific to Mask Tools.*, passed committee review with editorial changes as previously discussed. (See 6)
- Task Force is continuously working for *Doc.#4840, Revision to SEMI P45-0708, Specification for Job Deck Data Format for Mask Tools Type of Document: Revision to an existing Standard/Guideline.*

7.2 5 Year Review Task Force

Masao Otaki reported on progress for the 5 Year Review Task Force. Of note:

- Task Force is continuously drafting the below 2 documents and they are planning to submit the letter ballot for the earliest possible cycle.
 - *Doc.#5484, Revision to SEMI P22-0307, Guideline for Photomask Defect Classification and Size Definition.*
 - *Doc.#5537, Line Item Revision to SEMI P23-0200 (Reapproved 1107), Guidelines for Programmed Defect Masks and Benchmark Procedures for Sensitivity Analysis of Mask Defect Inspection Systems*

8 Old Business

8.1 Previous Meeting Action Items

Naoko Tejima reviewed the previous meeting action items.

Table 6 Previous Meeting Actions Items

<i>Item #</i>	<i>Assigned to</i>	<i>Details</i>
MP120828-2	5 Year Review Task Force	To draft the document of Doc. 5484, Revision to SEMI P22-0307 to submit it for the earliest possible cycle. ... Open
MP121211-1	5 Year Review Task Force	To draft the document of Doc. 5537, Line Item Revision to SEMI P23-0200 to submit it for the earliest possible cycle. ... Open
MP130828-1	5 Year Review Task Force	To draft the background statements for the Document #5484 and #5537. ... Open
MP140423-1	Mask Data Format for Mask Tools TF	To submit Doc. #5229, Revision to SEMI P44-0211, Specification for Open Artwork System Interchange Standard (OASIS) Specific to Mask Tools, for cycle 5, 2014. ... Close

9 New Business

None

10 Action Item Review

10.1 New Action Items

Naoko Tejima reviewed the new action items. These can be found in the New Action Items table at the beginning of these minutes.

11 Next Meeting and Adjournment

The next meeting of the Micropatterning Japan TC meeting is scheduled for Thursday, January 29, 2015, 15:30-17:00, at SEMI Japan, Tokyo, Japan.



Respectfully submitted by:
Naoko Tejima
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Minutes approved by:

Morihisa Hoga (Dai Nippon Printing), Co-chair	December 25, 2014
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Table 7 Index of Available Attachments #1

#	<i>Title</i>
1	JA_Micropatterning_Previous_Mtg_Minutes_141008
2	SEMI_Staff_Report_141008
3	Task_Force_Operation_Guideline_141008
4	Microlithography_NA_TC_Report_Oct2014_141008
5	Ballot_Report_for_5229_141008

#1 Due to file size and delivery issues, attachments must be downloaded separately. A .zip file containing all attachments for these minutes is available at www.semi.org. For additional information or to obtain individual attachments, please contact Naoko Tejima at the contact information above.